

PCT

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INTERNATIONAL PRELIMINARY EXAMINATION REPOR

WIPO PCT

(PCT Article 36 and Rule 70)

Applicant's or agent's file reference 220148 WO	FOR FURTHER ACTIO	N See Notificat Preliminary	tion of Transmittal of International Examination Report (Form PCT/IPEA/416)
International application No.	International filing date (day	month/year)	Priority date (day/month/year)
PCT/US03/26302	103/20302		19 September 2002 (19.09.2002)
International Patent Classification (IPC) (IPC(7): C03C 15/00; C23F 1/00; H01L 723R, 723I, 723IR, 723AN; 204/192.13 Applicant	21/00 and US Cl.: 156/345.1	345.24, 345.25, 3	345.35, 345.48, 345.49; 118/712, 713, 714, 6, 9, 569; 438/7, 8, 9, 14, 710
TOKYO ELECTRON LIMITED			
This international preliming Examining Authority and			y this International Preliminary Article 36.
2. This REPORT consists of	a total of 5 sheets, inclu	ling this cover sh	neet.
which have been ame	ended and are the basis for	this report and/or	e description, claims and/or drawings r sheets containing rectifications made ministrative Instructions under the PCT
These annexes consist of a total of sheets.			
3. This report contains indications relating to the following items:			
I Basis of the report			
II Priority			
III Non-establishm	a-establishment of report with regard to novelty, inventive step and industrial applicability		
F3			
5-7		41	
V Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement			
VI Certain documents cited			
VII Certain defects in the international application			
	tions on the international a		
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Date of submission of the demand	I	Date of completion	n of this report
20 April 2004 (19.04.2004)	2	4 September 2004	(24.09.2004)
Name and mailing address of the IPEA/I	US ,	uthorized officer	1 \ . / /
Mail Stop PCT, Attn: IPEA/US Commissioner for Patents		Luz L. Alejandro	1-1-1-
P.O. Box 1450 Alexandria, Virginia 22313-1450	1		,
Facsimile No. (703) 305-3230 Form PCT/IPEA/409 (cover sheet)(July 1		'elephone No. 703	-308-0001

INTERNATIONAL PRES	NARY EXAMINATION REPORT

Internation	olication No.	
PCT/US03	2 02	

I.	Basi	s of the report
1.	With	regard to the elements of the international application:*
	X	the international application as originally filed.
	岗	the description:
	لكا	pages 1-13 as originally filed
		pages NONE filed with the demand
		pages NONE , filed with the letter of
	\bowtie	the claims:
		pages 14-19 , as originally filed
		pages NONE , as amended (together with any statement) under Article 19 pages NONE , filed with the demand
		pages NONE , filed with the letter of
	X	the drawings:
	لاسكا	pages 1-9 , as originally filed
		pages NONE filed with the demand
1		pages NONE , filed with the letter of
	Ш	the sequence listing part of the description:
		pages NONE , as originally filed
		pages NONE , filed with the demand pages NONE , filed with the letter of .
2.	Wit	h regard to the language, all the elements marked above were available or furnished to this Authority in the
	lang	uage in which the international application was filed, unless otherwise indicated under this item.
	The	se elements were available or furnished to this Authority in the following language which is:
}		the language of a translation furnished for the purposes of international search (under Rule23.1(b)).
		the language of publication of the international application (under Rule 48.3(b)).
	Ш	the language of the translation furnished for the purposes of international preliminary examination (under Rules 55.2 and/or 55.3).
3.	With	h regard to any nucleotide and/or amino acid sequence disclosed in the international application, the mational preliminary examination was carried out on the basis of the sequence listing:
		contained in the international application in printed form.
		filed together with the international application in computer readable form.
		furnished subsequently to this Authority in written form.
		furnished subsequently to this Authority in computer readable form.
		The statement that the subsequently furnished written sequence listing does not go beyond the disclosure in the international application as filed has been furnished.
		The statement that the information recorded in computer readable form is identical to the written sequence listing has been furnished.
4.	\boxtimes	The amendments have resulted in the cancellation of:
		the description, pages NONE
		the claims, Nos. NONE
		the drawings, sheets/fig NONE
5.		This report has been established as if (some of) the amendments had not been made, since they have been considered to go beyond the disclosure as filed, as indicated in the Supplemental Box (Rule 70.2(c)).**
l tru	s repo	cement sheets which have been furnished to the receiving Office in response to an invitation under Article 14 are referred to in ort as "originally filed" and are not annexed to this report since they do not contain amendments (Rules 70.16 and 70.17). replacement sheet containing such amendments must be referred to under item 1 and annexed to this report.
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INTERNATIONAL PREDMINARY EXAMINATION REPORT

Internation plication No. PCT/USO. 12

V. Reasoned statement under Rule 66.2(a)(ii citations and explanations supporting suc	i) with regar h statement	d to novelty, inventive step or industria	al applicability;
1. STATEMENT			
Novelty (N)	Claims	5-7,16-20,25-27,29-31 and 33	YES
10.119 (4)	Claims	1-4, 8-15, 21-24, 28, 32	МО
Inventive Step (IS)	Claims	NONE	YES
	Claims	1-33	NO
Industrial Applicability (IA)	Claims	1-33	YES
	Claims	NONE	NO
2. CITATIONS AND EXPLANATIONS Please See Continuation Sheet			

Form PCT/IPEA/409 (Box V) (July 1998)

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TC1/0303	302

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(To be used when the space in any of the preceding boxes is not sufficient)

Claims 1-4, 8-15, 21-24, 28 and 32 lack novelty under PCT Article 33(2) as being anticipated by Koshimizu, U.S. Patent 5,290,383. Koshimizu shows the invention as claimed including process chamber comprising a viewing port coupled to the process chamber, wherein the viewing port comprises: a viewing window to permit optical access to the process chamber; a mounting to couple the viewing window to the process chamber; and a viewing window cleaning apparatus, comprising a RF source and an inductive coil as a plasma source, coupled to the mounting and disposed between the viewing window and the process chamber, and configured to form a cleaning plasma in a cleaning plasma region of the mounting; wherein the viewing window cleaning apparatus further comprises an impedance match assembly and a plasma generator; a gas injection system is coupled to the cleaning plasma region; and wherein the supporting section of the viewing window is configured to position the viewing window at a predetermined position relative to a position of the process chamber. For a complete description of the apparatus see fig. 26 and its description.

With respect to claims 9-14, note that the cleaning plasma etches by-products deposited on the viewing window through physical/chemical etching. Furthermore, the claims are directed to method limitations instead of apparatus limitations and since an apparatus is being claimed as the instant invention to method teachings are not considered to be the matter at hand, since a variety of methods can be done with the apparatus. The method limitations are viewed as intended uses which do not further limit, and therefore, do not patentably distinguish the claimed invention.

Regarding claims 28 and 32, Koshimizu discloses the claimed method of cleaning a viewing window for a process chamber.

Claims 5-7, 18-20, 25-27 and 29 lack an inventive step under PCT Article 33(3) as being obvious over Koshimizu, U.S. Patent 5,290,383 in view of Masuda et al., U.S. Patent 6,503,364 or Masuda et al., JP 2001-77092A.

Koshimizu is applied as above but does not expressly discloses an apparatus further comprising at least one array of magnets coupled to the mounting. Masuda et al. (both '364 and '092) discloses an apparatus comprising a viewing window having a mounting couple to it and further comprising an array of magnets for suppressing adhesion of deposits onto the window (see, for example, figs. 1-3 and their description, especially col. 8, lines 13-33). Therefore, it would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the apparatus of Koshimizu by further comprising an array of magnets in order to suppress adhesion of deposits in the window.

Claims 17 and 30 lack an inventive step under PCT Article 33(3) as being obvious over Koshimizu, U.S. Patent 5,290,383 in view of Chen et al., U.S. Patent 6,071,375 or Melvin et al., U.S. Patent 6,306,246.

Koshimizu is applied as above but does not expressly disclose wherein the gas injection system is configured to flow a gas into the cleaning plasma region so that a pressure is generated in the cleaning plasma region, the pressure substantially opposing a propagating direction of by-products. Chen et al. discloses an apparatus in which a gas injection system is configured to flow a gas into the a cleaning plasma region, around a viewing window, so that a pressure is generated in the cleaning plasma region, the pressure substantially opposing a propagating direction of by-products in order to avoid the accumulation of by-products particulates or other contaminants (see, for example, figs. 1-3, and col. 3-line 19 to col. 5-line 60). Additionally, Melvin et al. discloses an

Form PCT/IPEA/409 (Continuation Sheet) (July 1998)



Internation plication No. PCT/US03/20302

Supplemental Box		

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apparatus in which a gas injection system is configured to flow a gas into the a cleaning plasma region, around a viewing window, so that a pressure is generated in the cleaning plasma region, the pressure substantially opposing a propagating direction of by-products in order to avoid the accumulation of by-products particulates or other contaminants (see, for example, figs. 2-4, and their descriptions). Therefore, in view of these disclosures, it would have been obvious to one having ordinary skill in the art at the time the invention was made to modify the apparatus of Koshimizu as to comprise the a gas injection system configured to flow a gas into the cleaning plasma region so that a pressure is generated in the cleaning plasma region, the pressure substantially opposing a propagating direction of by-products in order to avoid the accumulation of by-products particulates or other contaminants.

Claims 16, 31 and 33 lack an inventive step under PCT Article 33(3) as being obvious over Koshimizu, U.S. Patent 5,290,383.
Koshimizu is applied as above but does not expressly disclose that the predetermined position in which the viewing window is positioned relative to the position of the chamber is selected so that a substantial amount of by-products do not travel to the viewing window. However, the it would have been an obvious choice of design to one of ordinary skill in the art to optimize the location/position of the viewing window relative to the process chamber during routine experimentation depending upon, for example, the amount of by-products avoided, and would not lend patentability to the instant application absent the showing of unexpected results.
Furthemore, Koshimizu does not expressly disclose etching the by-products using the specific claimed gases, however, the incorporation/use of such claimed gases in the teachings of the Koshimizu reference would have been obvious to one having ordinary skill in the art at the time the invention was made because such claimed gases are well know and used in the art as suitable etching gases.
NEW CITATIONS
orm PCT/IPEA/409 (Continuation Sheet) (July 1998)